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#29/CDA
4p/02

CONTINUED PROSECUTION APPLICATION (CPA) REQUEST TRANSMITTAL (Only for Continuation or Divisional Applications under 37 CFR 1.53(d))		
Address to: Assistant Commissioner for Patents Box CPA Washington DC 20231	Attorney Docket No.	Old Docket No. P97,0322 New No. 09794353-0005
	First Named Inventor	Mitsuhiro Nakamura
	Express Mail Label No.	EL834557024US
	Date:	November 12, 2001

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TC 1700

This is a request for a X continuation or divisional application under 37 CFR 1.53(d), (continued prosecution application (CPA)) of prior application number 08/809,463, filed on July 18, 1997, entitled "MULTILAYERED STRUCTURE FOR FABRICATING AN OHMIC ELECTRODE AND OHMIC ELECTRODE"

1. Enter the unentered Amendment - previously mailed on , under 37 CFR 1.116 in the prior non-provisional application.
2. X Preliminary Amendment attached.
3. This application is filed by fewer than all the inventors named in the prior application, 37 CFR 1.53(d)(4).
 - a. DELETE the following inventor(s) named in the prior non-provisional application:
 - b. The inventor(s) to be deleted are set forth on a separate sheet attached hereto.
4. A new power of attorney or authorization of agent (PTO/SB/81) is enclosed.
5. Information Disclosure Statement (IDS) is enclosed:
 - a. PTO-1449
 - b. Copies of IDS Citations

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CLAIMS AS FILED				
(1) FOR	(2) NUMBER FILED	(3) NUMBER EXTRA	(4) RATE	(5) BASIC FEE
TOTAL CLAIMS	19		18.00	0.00
INDEPENDENT CLAIMS	5	2	84.00	168.00
ANY MULTIPLE DEPENDENT CLAIMS? ()YES (X)NO				\$0.00
			TOTAL FILING FEE	\$908.00

01/28/2002 AWONDAF1 00000104 08809463

01 FC:131 740.00 OP
02 FC:102 168.00 OP

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6. Small entity status:

- a. ☐ A small entity statement is enclosed
- b. ☐ A small entity statement was filed in the prior non-provisional application and such status is still proper and desired.
- c. ☐ Is no longer claimed.

7. ☒ The Commissioner is hereby authorized to charge any additional fees or credit any overpayment to Deposit Account No. 19-3140. *A duplicate copy of this sheet is enclosed.*

8. ☒ A check in the amount of \$908.00 to cover the base filing fee is enclosed.

9. ☐ Other: An Extension of Time to File Response to Office Action of ☐ be extended for ☐ month(s) to ☐. A check in the amount of \$☐ to cover the three-month extension fee is enclosed.

10. ☐ The Commissioner is hereby authorized to charge the amount of \$ ☐ to cover the ☐-month extension fee to Deposit Account No. 19-3140. A duplicate copy of this sheet is enclosed for that purpose.

Respectfully submitted,

By: Christopher P. Rauch (Reg. 45,034)
Christopher P. Rauch
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November 12, 2001

When phoning re: this application
please call (312) 876-8000 Ext. 2606

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS: Mitsuhiro Nakamura et al. OLD DOCKET NO.: P97,0322
NEW DOCKET NO.: 09794358,0005
SERIAL NO. 08/809,463 GROUP ART UNIT: 2814
FILING DATE: July 18, 1997 EXAMINER: P. Cao
INVENTION: "MULTI-LAYERED STRUCTURE FOR FABRICATING AN
OHMIC ELECTRODE AND OHMIC ELECTRODE"

PRELIMINARY AMENDMENT
ACCOMPANYING CONTINUED PROSECUTION APPLICATION (CPA)

Hon. Assistant Commissioner for Patents
Washington, DC 20231

SIR:

This Preliminary Amendment accompanies a Continued Prosecution Application (CPA) and is filed in response to the Decision on Request for Rehearing of September 13, 2001. In the Decision on Request for Rehearing, the Board of Patent Appeals and Interferences granted the Applicants' request for a rehearing, yet affirmed their earlier Decision on Appeal to maintain the Examiner's final rejection of the claims.

Please enter the following amendment prior to examination of the above-identified Continued Prosecution Application (CPA).

IN THE CLAIMS

Please amend claims 1, 9, 10, and 19 as follows:

1. (Twice Amended) A multi-layered structure for fabricating an ohmic electrode, comprising a non-single crystal semiconductor layer comprising In and a film including at least a metal nitride film which are sequentially stacked on a III-V compound semiconductor body, wherein said metal nitride film is selected from the group consisting of a WN film, a WSiN film, a TaN film, a TaSiN film, a TiN film, a TiSiN film, and a TiON film.

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